

ABSTRACT

A lithographic apparatus includes an illumination system for providing a beam of radiation, a support structure constructed to support a patterning device, which serves to impart the projection beam with a pattern in its cross-section, a substrate table for holding a substrate, a projection system that projects the patterned beam onto a target portion of the substrate, and a reference frame with a position sensor and the substrate being located thereon. The apparatus further includes a heat transport system having a heating element, in thermal interaction with at least one of the projection system and the reference frame, for heat transport to or from at least one of the projection system and the reference frame, wherein the heat transport system, is coupled to a further frame which is mechanically isolated from the reference frame.